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REMARKS/ARGUMENTS

Claims 22-52 and 62-67 are pending in this application. By this Amendment, Applicant amends claims 22 and 38-40 and cancels claims 1-21, 53-61, 68, and 69.

Applicant affirms the election of claims 22-26, 29-33, 35-42, 44, 46, 47, 49, and 62-66. Applicant respectfully requests that the Examiner rejoin and allow withdrawn claims 27, 28, 34, 43, 45, 48, 50-52, and 67 when generic claims 22 and 40 are allowed. Applicant reserves the right to file a Divisional Application to pursue non-elected claims 1-21, 53-61, 68, and 69.

The Examiner rejected claims 22-26, 29-33, 36-42, 47, 63, 65, and 66 under 35 U.S.C. § 102(b) as being anticipated by Tanaka et al. (U.S. 6,251,712). The Examiner rejected claims 35, 44, 46, and 62 under U.S.C. § 103(a) as being unpatentable over Tanaka et al. The Examiner rejected claim 64 under U.S.C. § 103(a) as being unpatentable over Tanaka et al. in view of Zhang et al. (U.S. 5,481,121). It is noted that the Examiner did not reject claim 49 over the prior art nor indicate that claim 49 would be allowable if rewritten in independent form including all of the features of the base claim and any intervening claims. Applicant respectfully traverses the rejections of claims 22-26, 29-33, 35-42, 44, 46, 47, and 62-66.

Claim 22 has been amended to recite:

"A method for manufacturing a semiconductor device, comprising the steps of:

providing an amorphous semiconductor film including a catalyst element in at least a portion thereof, the catalyst element being capable of promoting crystallization of the amorphous semiconductor film;

performing a first heat treatment on the amorphous semiconductor film so as to crystallize at least a portion of the amorphous semiconductor film, thereby obtaining a semiconductor film including a crystalline region;

patterning the semiconductor film to form an island-shaped semiconductor layer including the crystalline region;

forming a gate insulating film on the island-shaped semiconductor layer; selectively thinning or selectively removing a portion of the gate insulating film that is located outside a region of the island-shaped semiconductor layer where a channel region, a source region and a drain region are formed;

forming a gettering region capable of attracting the catalyst element

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**in a region outside the region of the island-shaped semiconductor layer where the channel region, the source region, and the drain region are formed;**

doping the crystalline region of the island-shaped semiconductor layer with an impurity for forming the source region and the drain region; and  
performing a second heat treatment so as to move at least a portion of the catalyst element in the island-shaped semiconductor layer to the gettering region." (emphasis added)

Applicant's claim 40 recites method steps similar to the method steps recited in claim 22, including the above emphasized method step. Support for the above amendments can be found in, for example, paragraphs [0113] and [0114] on pages 44 and 45 of the originally filed specification.

With the improved method steps of claims 22 and 40, Applicant has been able to simplify the manufacturing process of a semiconductor device by providing a dedicated gettering region separate from the source region and the drain region in order to optimize the doping of the source region and the drain region and without adversely increasing the resistance of the source and drain regions so that they will no longer function as a source region and a drain region while significantly improving the gettering capability of the gettering region (see, for example, paragraphs [0012] through [0014], [0115] and [0116] of the originally filed specification).

The Examiner alleged that Tanaka et al. teach "forming a gettering region capable of attracting the catalyst element in a region where the gate insulating film on the island-shaped semiconductor layer has been thinned or removed (see figs. 4E-4F); simultaneously doping the crystalline region of the island-shaped semiconductor layer with an impurity for forming the source region and the drain region (423, 424, 425, 426)."

Claim 22, and similarly claim 40, has been amended to recite the step of "forming a gettering region capable of attracting the catalyst element in a region **outside the region** of the island-shaped semiconductor layer where the channel region, the source region, and the drain region are formed."

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In contrast to Applicant's claims 22 and 40, Tanaka et al. teach gettering (Fig. 4E) all of the source and drain regions (417-426) with phosphorous ions. See, for example, lines 22-27 of column 10, lines 31-60 of column 11, and lines 18-29 of column 12 of Tanaka et al.

Thus, Tanaka et al. fail to teach or suggest the step of "forming a gettering region capable of attracting the catalyst element in a region outside the region of the island-shaped semiconductor layer where the channel region, the source region, and the drain region are formed," as recited in Applicant's claim 22, and similarly in claim 40.

Accordingly, Applicant respectfully requests reconsideration and withdrawal of the rejection of claims 22-26, 29-33, 36-42, 47, 63, 65, and 66 under 35 U.S.C. § 102(b) as being anticipated by Tanaka et al.

Zhang et al. was relied upon to allegedly cure the deficiencies of Tanaka et al. However, Zhang et al. fail to teach or suggest the step of "forming a gettering region capable of attracting the catalyst element in a region outside the region of the island-shaped semiconductor layer where the channel region, the source region, and the drain region are formed," as recited in Applicant's claim 22, and similarly in claim 40.

Accordingly, Applicant respectfully submits that Tanaka et al. and Zhang et al., applied alone or in combination, fail to teach or suggest the method steps recited in Applicant's claims 22 and 40.

In view of the foregoing amendments and remarks, Applicant respectfully submits that claims 22 and 40 are allowable. Claims 23-26, 29-33, 35-39, 41, 42, 44, 46, 47, 49, and 62-66 depend upon claims 22 and 40, and are therefore allowable for at least the reasons that claims 22 and 40 are allowable.

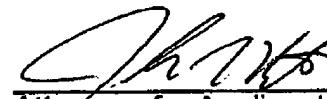
In addition, as noted above, claims 22 and 40 are generic. Accordingly, Applicant respectfully requests that the Examiner rejoin and allow withdrawn claims 27, 28, 34, 43, 45, 48, 50-52, and 67 when generic claims 22 and 40 are allowed.

In view of the foregoing amendments and remarks, Applicant respectfully submits that this application is in condition for allowance. Favorable consideration and prompt allowance are solicited.

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The Commissioner is authorized to charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account No. 50-1353.

Respectfully submitted,

  
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Attorneys for Applicant

Joseph R. Keating  
Registration No. 37,368

Dated: February 2, 2006

Peter Medley  
Registration No. 56,125

**KEATING & BENNETT, LLP**  
8180 Greensboro Drive, Suite 850  
Tyson's Corner, VA 22102  
Telephone: (703) 637-1480  
Facsimile: (703) 637-1499

Stephen R. Funk  
Registration No. 57,751